



For immediate release
17 April 1997

New Chemical Society Formed In Hong Kong

The Hong Kong International Chemical Sciences (HK-ICS), a chapter of the American Chemical Society, will be inaugurated at the Hong Kong University of Science and Technology on 23 April.

HK-ICS hopes to promote the work of the territory's chemical scientists at an international level, working closely with the existing Hong Kong Chemical Society. The American Chemical Society is the world's largest single-discipline professional society, with more than 140,000 members.

"The new society will promote public interest in the chemical sciences," said Prof Nai-Teng Yu, chairman of HK-ICS and professor of chemistry at HKUST. "We hope to establish scholarship and awards programs and forge academic and industrial links between East and West."

The new chapter will be inaugurated with a keynote address by Prof Paul H.L. Walter, president-elect of the American Chemical Society. Other speakers include Prof Chia-Wei Woo, president of HKUST, and distinguished guests from chemical societies in Hong Kong, Taiwan, Singapore and Japan.

The ceremony will be followed by a mini-symposium in honor of Prof Hiroyuki Hiraoka, on the occasion of his 65th birthday. A renowned expert in photochemistry, Prof Hiraoka is currently acting head of the Department of Chemistry at HKUST. His technique for producing diamond films through laser ablation earned the University its first patent, granted in 1994.

Event: Inauguration Ceremony: Hong Kong International Chemical Sciences

Date: Wednesday, 23 April 1997

Time: Ceremony: 10 am - 12 noon

Symposium: 2 - 5:30 pm

Venue: Council Chamber, 7/F, Hong Kong University of Science and Technology, Clear Water Bay, Kowloon

Note to Editors:

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